

NEW

SUPERCritical 6" WAFER CPD MEMS DRYER **AUTOMEGASAMDRI®-915B, SERIES C**

UNPARALLELED VERSATILITY AND LOW LCO₂ CONSUMPTION

tousimis




- The **Automegasamdri®-915B, Series C** maintains tousimis® process quality and achieves a small facility foot print by utilizing an efficient "closed loop refrigeration and waste alcohol collection" engineered design.*
- 35 years of tousimis® CPD experience enables smooth operation and precise control. HF Compatible Wafer Holders* and Chamber Inserts* are provided allowing anti-stiction MEMS processing of various wafer sizes and die.

SUPERCritical Automegasamdri®-915B, Series C
Catalog# 8785D (Process Various Wafer Sizes up to 6in)



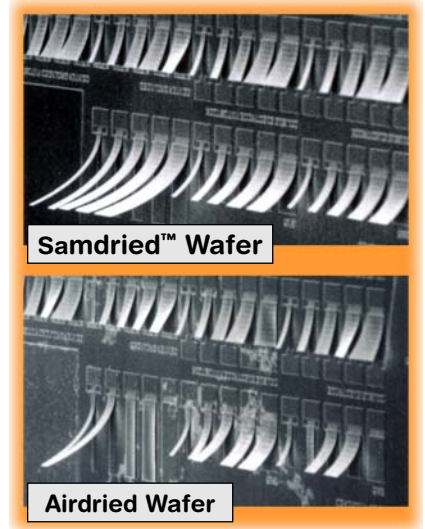
- **40% Less LCO₂ Consumption.¹**
- **Process up to 5 wafers in Less than 1 hour.**
- **All inclusive Small Foot Print design.**
- **Minimal installation Site Preparation required.**
- **On Site Start-Up and User Training included.²**

FEATURES

- High efficiency internal closed loop refrigeration.* (22°C to operational in less than 4 minutes)!
- Post-Purge-Filter easily accessible for maintenance ease.*
- The patented internal SOTER™ condenser* quietly captures and separates CO₂ exhaust and waste alcohols.
- Unique chamber inserts* enable variance of chamber I.D. maximizing efficiency in LCO₂ consumption, process time, and providing multiple size wafer process capability!
- Process up to 5 x 6" wafers per process run. Also comes with additional HF Compatible Wafer Holders* to process 5 x 4", 5 x 3", 5 x 2" diameter wafers or 5 x 10mm square die (tousimis® HF compatible Wafer Holders* may be used to etch and process your wafers minimizing handling).
- Chamber illumination with viewing window facilitates chamber status visualization.*
- Microprocessor controller allows for complete automatic processing.*
- All internal surfaces are inert to CO₂ and ultrapure alcohols.
- Repeatable operating parameters insuring "reproducibility" of results.
- Static pressure control module helps insure automatic safe pressure stability.
- Internal filtration system delivers clean LCO₂ into process chamber down to 0.4µm.
- Control panel LED's instantly indicate process mode at a glance.
- Clean room static-free compatible design.
- All electronic components meet CE, UL and/or U.S. Military Specifications.

SPECIFICATIONS

- Cabinet: 21" (53.3cm) Width x 34" (86.4cm) Depth x 45" (114.3cm) Height
- System Set-Up Area Footprint: 27" (68.6cm) Width x 38" (96.5cm) Depth
- Chamber size: 6.50" I.D. x 1.25" Depth / Chamber volume: 679 ml
- Temperature gauge range: -30°C to 60°C, Pressure gauge range: 0 to 2,000 psi
- 120V / 50-60Hz (Other voltage units also available. Please Inquire)
- LCO₂ flow is controlled through Micro Metering Valves with Vernier handles for easily control flow rates.*



- LCO₂ High Pressure braided stainless steel inert Teflon® lined hose. 10ft (~ 3m) long for clean room operation (Other lengths available upon request at a nominal charge).
- LCO₂ external combination filter assembly (#8784) for water / oil / particulates (down to 0.5µm) pre-installed onto the chamber LCO₂ supply high-pressure hose.
- Tool set included for connecting LCO₂ chamber supply line.
- Static free exhaust tubing for all exhaust outlets.
- Internal stainless and nickel scintered filtration systems incorporated to protect lines, wafers, and valves down to 0.4µm.
- Spare chamber O-ring (3), chamber lamps (2), and slo-blow fuses.
- Complete wafer size process flexibility! 4 chamber inserts* enable 6.5" chamber ID reduction down to smaller chamber ID sizes for processing wafers and die from a range including: 6", 4", 3", 2", and 1.25" ! Allows for multiple wafer size drying.
- 6", 4", 3", 2" diameter wafer holders and 10mm square die holders included. Holders are HF compatible and can holds up to 5 wafers or die each.
- 2 year warranty on all parts and labor. Free lifetime technical support consultation by our scientific staff.

¹ Compared with tousimis Automegasamdri®-915B, Series B

Note: Actual delivered model or accessories may vary slightly, as advancements are being constantly applied.

² Available for most countries. Contact tousimis for details.

* Most Automegasamdri® feature U.S. patents (# 6,493,964, #6,678,968) or patents pending.

OPTIONAL ACCESSORIES

Catalog #	Description
8760-03	Knurl Nut for Automegasamdri®-915B, Series C
8760-41	3 AMP Fuse for Automegasamdri®-915B, Series C
8760-42	8 AMP Fuse for Automegasamdri®-915B, Series C
8770-10	Lamp, 120V/60Hz
8770-32	High Pressure Hose, 5 ft
8770-33	High Pressure Hose, 10 ft
8770-HPS	High Pressure Hose, Custom Length Up To 10m (33ft)
8770-47	Flow Meter- Use with Automegasamdri®-915B (100SCFH)
8784	LCO ₂ Filter Housing for 8784A Filter Element
8784A	Replacement LCO ₂ Filter Element for 8784 Filter Housing
8784B	O-Ring for 8784 Filter Housing Seal
8784-05	Gasket for LCO ₂ Tank Connect
8783	LCO ₂ Filter Adapter Kit
8770-51T/915B	Teflon® O-Ring for Automegasamdri®-915B
8770-51T/915B-BR	Backing Ring for tousimis® Automegasamdri®-915B
8770-54	LCO ₂ Tank Scale, w/ Remote LCD Display (400lb capacity)
8770-55	LCO ₂ Tank Heater
8770-56A	Step-Down Transformer, 220V → 110V
8770-57A	Step-Up Transformer, 100V → 120V
8770-80	Chamber Lid for tousimis Automegasamdri®-915B
8770-83A	Internal 0.5µm 316SS Particulate Line Filter
8770-83B	0.5µm Particulate Filter Element for LCO ₂ T-Filter or External Purge Line Filter
8785-47A	HC-50 Chiller Fluid
8768A	HF Compatible Wafer Holder for 6" Diameter Wafers
8768F	HF Compatible Wafer Holder for 5" Diameter Wafers
8768B	HF Compatible Wafer Holder for 4" Diameter Wafers
8768C	HF Compatible Wafer Holder for 3" Diameter Wafers
8768D	HF Compatible Wafer Holder for 2" Diameter Wafers
8768G	HF Compatible Wafer Holder for 1" Diameter Wafers
8768E	HF Compatible Chip Holder for 5 x 10mm Square Die

Visit tousimis.com for more information.

¹ Compared with tousimis Automegasamdri®-915B, Series B

² Available for most countries. Contact tousimis for details.*

* Most Automegasamdri® feature U.S. patents (# 6,493,964, #6,678,968) or patents pending.

Note: Actual delivered model or accessories may vary slightly, as advancements are being constantly applied.